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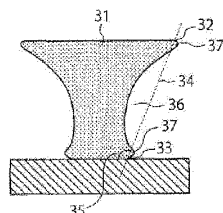
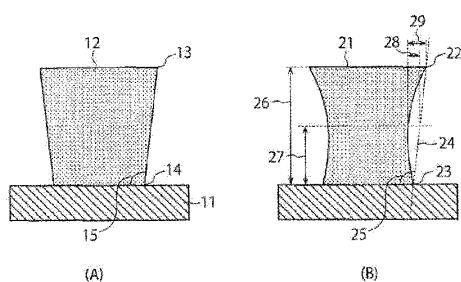
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(54) Title: POSITIVE TYPE LIFT-OFF RESIST COMPOSITION AND METHOD FOR MANUFACTURING RESIST PATTERN
USING THE SAME



(C)

Figure 1

(57) Abstract: [Problem] A positive type lift-off resist composition is provided. [Means for Solution] A positive type lift-off resist composition comprising a polymer (A) having a certain structure and cLogP of 2.76 to 3.35, a photoacid generator (B) and a solvent (C).

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